

## EAST Search History

## EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S3	4	((("5,314,569") or ("6,346,189")).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/25 09:16
S7	2	("20020136681").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/25 09:19
S8	2	("20060292870").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/25 12:02
S9	30	(calibrated pore\$1)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 13:27
S12	66	(PRIBAT, DIDIER).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:49
S13	4	(WEGROWE, JEAN-ERIC).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:49
S14	10	(WADE, TRAVIS).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:49

S15	8	(WEGROWE).in.	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 15:54
S17	804	(single crystal\$4 or single-crystal\$4) near2 zone	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 17:03
S18	79	(single crystal\$4 or single-crystal\$4) near2 zone and (alumina or aluminium oxide)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/25 17:03
S29	270	(epitax\$5) and (((electrochemical or electrochemical or electroplating or electro-plating) near2 (growth or deposition)) and (aluminium) and (cobalt))	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 10:40
S33	975	alumina and nanoporous	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:19
S36	371	(alumina or sapphire or aluminium oxide) and nanoporous and (nanowire or nanotube or nanorod)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:21
S37	2	("6,359,288").PN.	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/11/26 13:39
S40	1	(anodic oxidation) and (single crystal aluminium substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:51
S41	1	(anodic oxidation) and (single crystal near2 aluminium substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:52

S42	1	(anodic oxidation) and (single crystal near4 aluminium substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:52
S43	1	(anodic oxidation) and (single crystal near4 aluminium near2 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:53
S44	1	(anodic oxidation) and (single crystal near4 aluminium near4 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:53
S45	4	(anodic oxidation) and (single crystal same aluminium near4 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:53
S47	2	(anodic oxidation or anodization) and (single crystal near4 aluminium near4 substrate) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:54
S48	19	(anodic oxidation or anodization) and (single crystal near4 aluminium) and (alumina or aluminium oxide or sapphire)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 13:56
S49	12	(anodic oxidation or anodization) and (single crystal aluminium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 14:01
S50	37	(advantage\$1 or benefit\$1) same (single crystal aluminium)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/11/26 15:25
S51	5	("3929527"   "4325776"   "4554030"   "5216271"   "5262361").PN. OR ("5782997").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2008/11/26 15:27

S63	10	(advantage\$1 or benefit\$1) same (single crystal substrate) and (anodic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 07:30
S64	632	(advantage\$1 or benefit\$1) same (single crystal substrate) NOT S63	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 07:34
S65	2	single crystal aluminium substrate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 07:35
S62	886	((carbon nanotubes) or (nanowires)) and (porous) and catalyst and (aluminium or aluminum) and (@ad<"20041012" or @riad<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 08:42
S63	17	S62 and diffusion barrier	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:03
S64	129	S62 and electroplating	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:08
S66	148	S62 and (chemical vapor deposition with catalyst)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:08
S67	14	single crystal aluminium and monocrystalline silicon	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:23
S69	385	aluminium (deposition or thin film or metal film) and (monocrystalline or monocrystalline or single crystal or single-crystal) (silicon or substrate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:33

S70	310	aluminium (deposition or thin film or metal film) and (monocrystalline or monocrystalline or single crystal or single-crystal) (silicon or substrate) and (@ad< "20031013")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:34
S71	325	S62 and barrier	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:41
S72	48	S62 and barrier same catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:42
S73	1644	((carbon nanotubes) or (nanowires) or nanorods) and (porous or nanoporous or nano-porous) and catalyst and (@ad< "20041012" or @rlad< "20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:43
S74	37	S73 and barrier with catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 09:43
S80	20	((anneal or annealed or annealing) same catalyst) and (magnetic field) and (carbon nanowire or nanotube) and (@ad< "20031013") NOT drug NOT skin NOT inkjet	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 10:53
S81	20	"6,894,359"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 12:33
S84	101	nanotube and nanoporous and transistor and (@ad< "20031013" or @rlad< "20031013")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 12:35

S85	2	("7,189,435").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/01 12:40
S87	2	("20020158342").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/01 12:40
S88	234	S73 and (chemical vapor deposition with (catalyst or cobalt))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 14:18
S101	712	silicon same diffusion same aluminium same titanium nitride same barrier and (@ad<"20031013")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/01 15:17
S107	1647	((carbon nanotubes) or (nanowires) or nanorods) and (porous or nanoporous or nano-porous) and catalyst and (@ad<"20041012" or @riad<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:44
S108	1	S107 and (chemical vapor deposition with (catalyst or cobalt) with bottom with pore)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:44
S109	5	S107 and ((chemical vapor deposition or CVD) with (catalyst or cobalt or Co) with bottom with pore)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:45
S110	25	S107 and ((chemical vapor deposition or CVD) with (catalyst or cobalt or Co) with (bottom or pore))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:46
S111	42	carbonyl metal and catalyst and chemical with deposition	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 08:57

S112	2	("5102647").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/02 09:05
S113	1060	cobalt with chemical with deposition	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:23
S114	7	cobalt with pore with chemical with deposition	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:23
S118	16	cobalt same pore with chemical with deposition NOT S114	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:47
S120	102	cobalt and pore with chemical with deposition NOT S114 NOT S118	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:48
S121	83	cobalt and pore with chemical with (vapor or gas) with deposition NOT S114 NOT S118	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 09:48
S122	2	("6362011").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/02 09:49
S128	67	nanowire and catalyst and alumina and (nanopore or nanoporous) and (@AD<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/12/02 14:42
S129	10	((("4,472,533") or ("5,174,883") or ("5,198,112") or ("5,202,290") or ("5,581,091,"))).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/12/02 14:49

Si134	238	(977/843).CCL5.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/04 14:30
Si135	19	(977/893).CCL5.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/04 14:30
Si136	8	("5322196"   "6146227"   "6597090"   "6627842"   "6827979"   "7002820"   "7189940"   "7419887").PN. OR ("7538015").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/06/04 15:05
Si137	18	("20010028872"   "20020114949"   "20020117659"   "20020130311"   "20020172820"   "20020175408"   "20020178846"   "20030089899"   "20030132461"   "20040033339"   "20040043208"   "20060032526"   "5997958"   "6231744"   "6278231"   "6359288"   "6401526"   "6709929").PN. OR ("7348670").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/06/04 15:21
Si138	21	(OsI or Osium) with barrier with (Co or cobalt) with (Si or silicon)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 10:13
Si139	50	(OsI or Osium) with barrier with (Si or silicon)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 10:40
Si140	82	cvd with cobalt with catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 11:46
Si141	3	catalyst precursor and cobalt	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 11:56
Si144	70	carbonyl same cvd and nanotube	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:03



S145	1561	nanotube and FET	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:37
S146	1413	carbon nanotube and FET	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:37
S147	187	carbon nanotube and FET and template	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 12:37
S148	39	("20020153160"   "20030148562"   "20030155591"   "20030178601"   "20030179559"   "20040004235"   "20040149979"   "20040224490"   "20040232426"   "20040233649"   "20040253741"   "20050012163"   "20050029654"   "20050051805"   "20050056826"   "20050095780"   "20050116257"   "20050145838"   "20050156203"   "20060192231"   "6129901"   "6423583"   "6465813"   "6566704"   "6590231"   "6707098"   "6740910"   "6759693"   "6798000"   "6809361"   "6815294"   "6830981"   "6833567"   "6852582"   "6855603"   "6866891"   "6891227"   "6927982"   "7265376").PN. OR ("7462890").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2009/06/05 13:49
S149	6	US-6914256-\$.DID. OR US- 20070113779-\$.DID. OR US- 20050276743-\$.DID. OR US- 20050156180-\$.DID. OR US- 20040144985-\$.DID. OR US- 20030215865-\$.DID.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2009/06/05 14:34
S151	252	(977/932).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15

Si152	89	(977/936).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15
Si153	126	(977/937).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15
Si154	108	(977/938).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 16:15
Si155	26	electrode with extension with pore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:00
Si156	0	gate with extension with pore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
Si157	0	gate with extension with nanopore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
Si158	0	gate with (extension or extending) with nanopore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
Si159	33	gate with nanopore	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:10
Si161	33	gate same nanopore not Si159	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:32
Si162	2	((("5,581,091") or ("6,034,468")).FN.	US-PGPUB; USPAT; USOCR	OR	OFF	2009/06/05 17:33
Si165	107	nanotube and fet and (@ad<"20040101") and (AAO or aluminium oxide or alumina)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2009/06/05 17:55
Si166	273	(977/843).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/04/07 20:01

S167	335	(977/842).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/04/07 20:02
S168	132	(423/447.5).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/04/07 20:04
S169	64	("4472533"   "5693207").PN. OR ("6129901").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 20:06
S170	20	("20030119034"   "20030160556"   "20030165418"   "20040043148"   "20040232426"   "20050170089"   "20050276743"   "5863601"   "6129901"   "6278231"   "6325909"   "6515339"   "6628053"   "6737939"   "6803840"   "6821911").PN. OR ("7115306").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 20:14
S171	68	("5773921"   "5973444"   "6097138").PN. OR ("6628053").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 20:33
S172	2327	crystal structure with (alumina or sapphire or aluminium oxide)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:23
S173	1945	crystal structure with (alumina or sapphire or aluminium oxide with Trigonal)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:24
S174	16	crystal structure with (alumina or sapphire or aluminium oxide) with Trigonal	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:24
S175	152	crystal structure with (alumina or sapphire or aluminium oxide) with (Trigonal or single crystal)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:25
S176	17	crystal structure with (alumina or sapphire or aluminium oxide) with (Trigonal or (single crystal with anodic))	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:25
S177	1	crystal structure with (alumina or sapphire or aluminium oxide) with (single crystal with anodic)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:26
S178	5	(alumina or sapphire or aluminium oxide) with (single crystal with anodic)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:27
S179	5	(alumina or sapphire or aluminium oxide or anodic aluminium) with (single crystal with anodic)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/04/07 21:28

SI80	6151	(alumina or sapphire or aluminium oxide or anodic aluminium) with (single crystal)	US-PGPUB; USPAT; USOOR	ADJ	ON	2010/04/07 21:29
SI81	9831	(alumina or sapphire or aluminium oxide or anodic aluminium) with (single crystal) with anodic or anodization	US-PGPUB; USPAT; USOOR	ADJ	ON	2010/04/07 21:29
SI82	6	(alumina or sapphire or aluminium oxide or anodic aluminium) with (single crystal) with (anodic or anodization)	US-PGPUB; USPAT; USOOR	ADJ	ON	2010/04/07 21:29
SI84	9	(sputtering with single crystal with zinc) NOT (sputtering with single crystal with zinc oxide)	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 14:36
SI85	17	(sputtering with single crystal with copper) NOT (sputtering with single crystal with copper (oxide or sulfide or nitride))	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 14:39
SI87	3	Single Crystal Aluminum with anodic	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:39
SI88	13	Single Crystal with Aluminum with anodic	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:40
SI89	6	epitaxial with Aluminum with anodic	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:42
SI90	6	epitaxial with Aluminum with sputter	US-PGPUB; USPAT; USOOR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:43

SI91	3	epitaxial with copper with sputter	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:45
SI92	4044	single crystal growth	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:46
SI93	747	single crystal aluminum	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:46
SI94	60	single crystal aluminum and sputter	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:46
SI95	2	single crystal aluminum with sputter	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:46
SI96	2	single crystal aluminum with anodization	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:46
SI97	3	single crystal aluminum with (anodization or anodic)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 15:47
SI98	30	epitaxial with catalyst and nanowire	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 16:34
SI99	215	epitaxial with catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 16:40

S200	30	S199 and S198	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/08 16:40
S201	65495	cobalt with catalyst	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:36
S202	7	cobalt with catalyst with epitax\$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:36
S203	17	cobalt with catalyst same epitax\$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:38
S204	11	cobalt with catalyst same epitax\$3 and (@AD<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:39
S205	8	cobalt with (pore or hole) same epitax\$3 and (@AD<"20041012")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:41
S206	12	cobalt with (pore or hole) and epitax\$3 and (@AD<"20041012") and ("977").CLAS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:42
S207	68	cobalt and (pore or hole) and epitax\$3 and (@AD<"20041012") and ("977").CLAS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:43
S208	56	cobalt and (pore or hole) and epitax\$3 and (@AD<"20041012") and ("977").CLAS. NOT S206	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/04/09 13:44

S209	1	("7244456").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/04/09 15:37
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